In re Appl. No. 08/875,916

REMARKS

Claims 26-39 presently appear in this case. No claims have been allowed. The Official Action of December 28, 2000, has now been carefully studied. Reconsideration and allowance are respectfully urged.

Claims 10-14, 17-22, and 25-29 are rejected under 35 U.S.C. 112, second paragraph, for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

This rejection is respectfully traversed. The claims have been amended and rewritten to conform to the requirements of 35 U.S.C. 112.

New drawings Figures 1 and 2 are submitted to correct typographical errors in the numbers.

In view of the above, it is respectfully submitted that the claims are now in condition for allowance, and favorable action thereon is earnestly solicited.

Respectfully submitted,

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"Version with markings to show changes"

(Amended) The process according to claim 1335 wherein the substance flows fed to and carried off from the reaction cell (50) with external load resistor (56) and connected activation source (57) are formed into an isobaric, ternary substance circuit with the external thermal substance decomposition and external phase separation by the allocation of a heated solution heater (51), a gas vapor enricher (52) combined with a phase separator, a phase separator (53), a solution pump (54) and a gas compressor (55), whereby the twophase mixture (S)r. (G,V)p carried off from the reaction cell (50) is fed to the phase separator (53) and the phase (S)r and (G,V)p are separated, the vapor depleted gas (G,V)p carried off at the head of the phase separator (53) is united with the moderately vapor-depleted gas (G,V)m carried off from the reaction cell and the mixture (G,V)x is fed by the gas compressor (55) to the gas vapor enricher (52) and in the gas vapor enricher is conveyed towards the heated and vapordepleting solution (S)r with vapor uptake and the vaporenriched gas (G,V)r carried off at the head of the gas vapor enricher (52) is fed again to the reaction cell (50), while the vapor-enriched solution (S)r carried off at the bottom of the phase separator (53) is conveyed by the solution pump (54) through the solution heater (51) and introduced at the head into the gas vapor enricher (52) and the vapor-depleted

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solution (S)p carried off at the bottom of the gas vapor enricher (2) is fed again to the reaction cell (50).

(Amended) The process according to claim 2032 28. wherein the substance flows fed to and carried off from the galvanic reaction cell (40) with external load resistor (41) are formed into an isobaric, ternary substance circuit with external thermal substance decomposition and external phase separation thereby that a heated gas vapor enricher (42) combined with a phase separator, a solution recuperator (43), a solution cooler (44), a phase separator (45), a solution pump (46), and a gas compressor (47), whereby the tow-phase mixture (S)r, (G,V)p carried off from the reaction cell (40) is fed to the phase separator (45) and the phases (S)r and (G,V)p are separated, the vapor-depleted gas (G,V)p carried off at the head of the phase separator (45) is united with the moderately vapor-depleted gas (G,V)m carried off from the reaction cell and the mixture (G,V)x is fed by the gas compressor (47) to the gas vapor enricher (42) and in the gas vapor enricher is conveyed towards the heated vapor-depleting solution (s)r with vapor uptake and the vapor-enriched gas (G,V)r carried off at the head of the gas vapor enricher (42) is fed again to the reaction cell (40), while the vaporenriched solution (S)r carried off from the phase separator (45) is conveyed by the solution pump (46) through the

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secondary side of the solution recuperator (43)(41) and introduced at the head into the gas vapor enricher (42) and the vapor-depleted solution (S)p is carried off at the bottom of the gas vapor enricher (42), passed through the primary side of the solution recuperator (43) and through the solution cooler (44) and fed again to the reaction cell (40).